

What is claimed is:

1. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film.

2. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the thickness of the first levelling film is  $0.1\ \mu\text{m}$  or more and less than  $1.5\ \mu\text{m}$ .

3. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the thickness of the second levelling film is from  $0.1\ \mu\text{m}$  to  $2.9\ \mu\text{m}$  inclusive.

4. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the total thickness of the first levelling film and the second levelling film is from  $0.2\ \mu\text{m}$  to  $3.0\ \mu\text{m}$  inclusive.

5. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the first levelling film and the second levelling film are insulating films formed by spin coating.

6. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the first levelling film and the second levelling film are made of any of a polyimide resin, an acrylic resin, a resin containing a siloxane structure, and an inorganic SOG material.

7. A method of fabricating a display device, wherein the thickness of a first levelling film formed above a wiring is thinner than that of a second levelling film formed on the first levelling film, and wherein the first levelling film and the second levelling film are made of the same material.